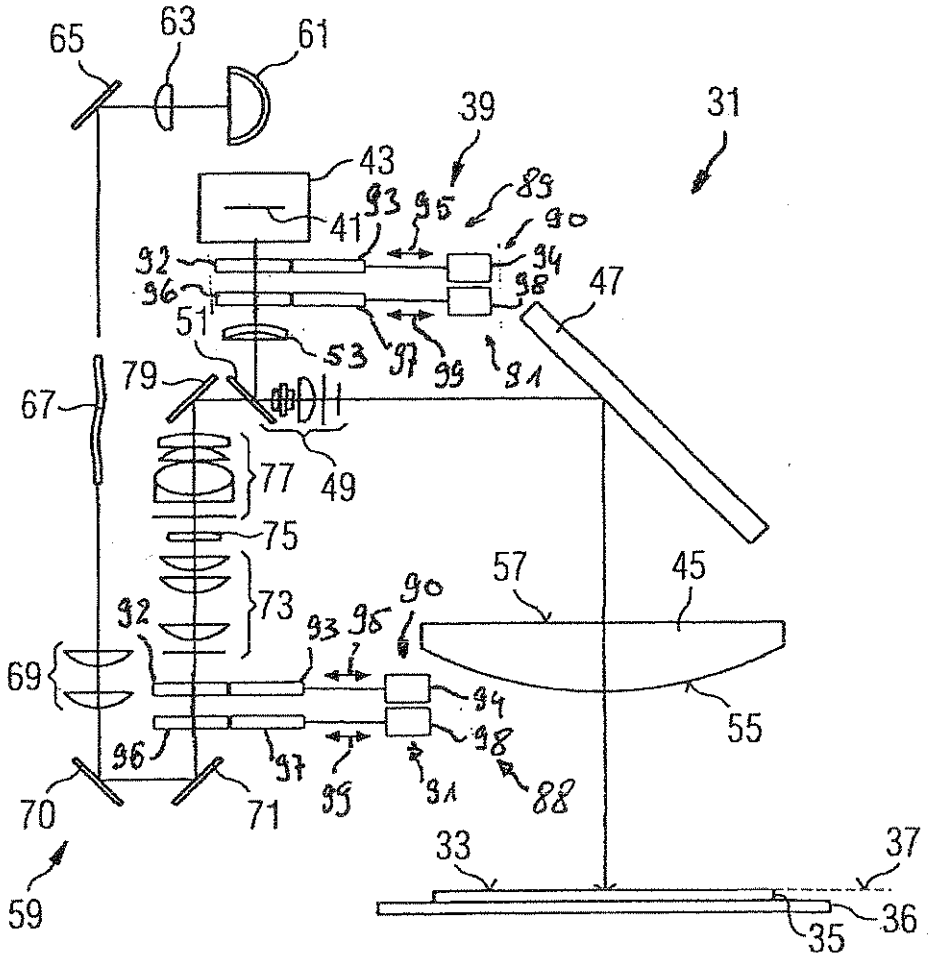

65
63
61
39
31
43
41
93
95
89
90
92
94
96
98
47
51
53
97
99
91
79
67
49
77
75
73
57
45
69
55
70
71
88
59
33
37
35
36

Fig. 1

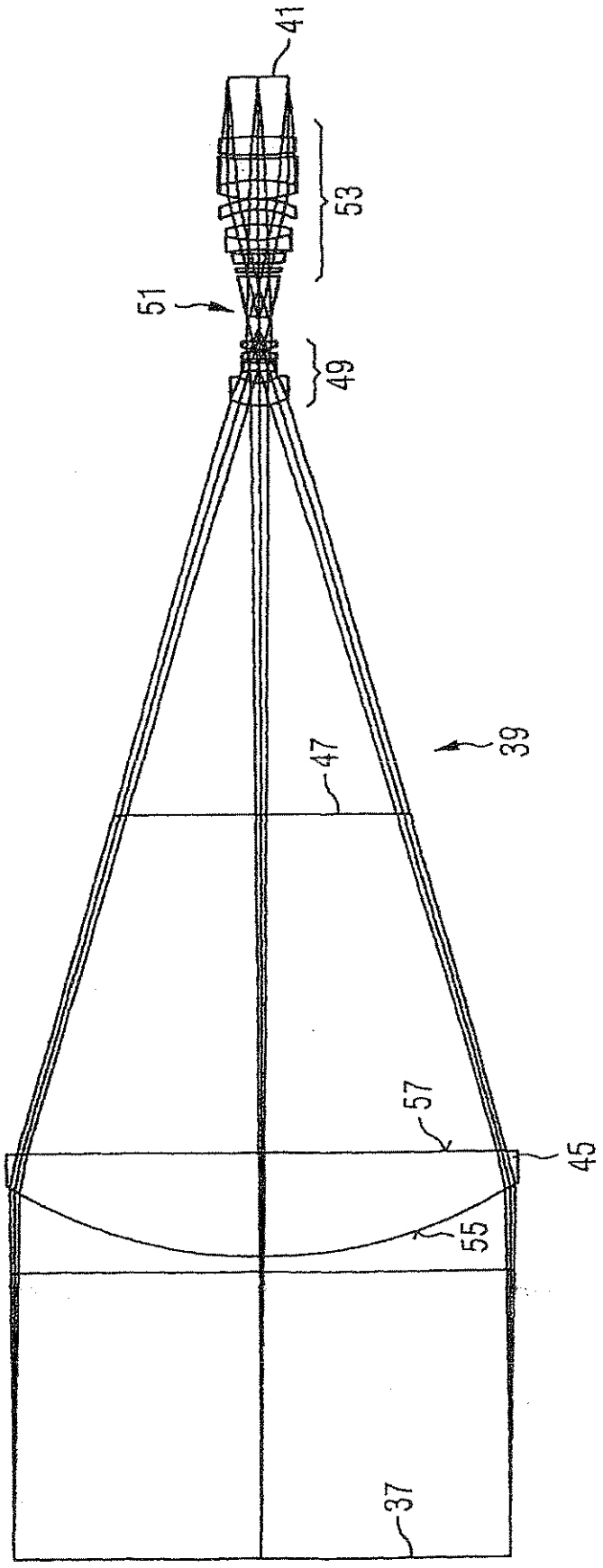


Fig. 2

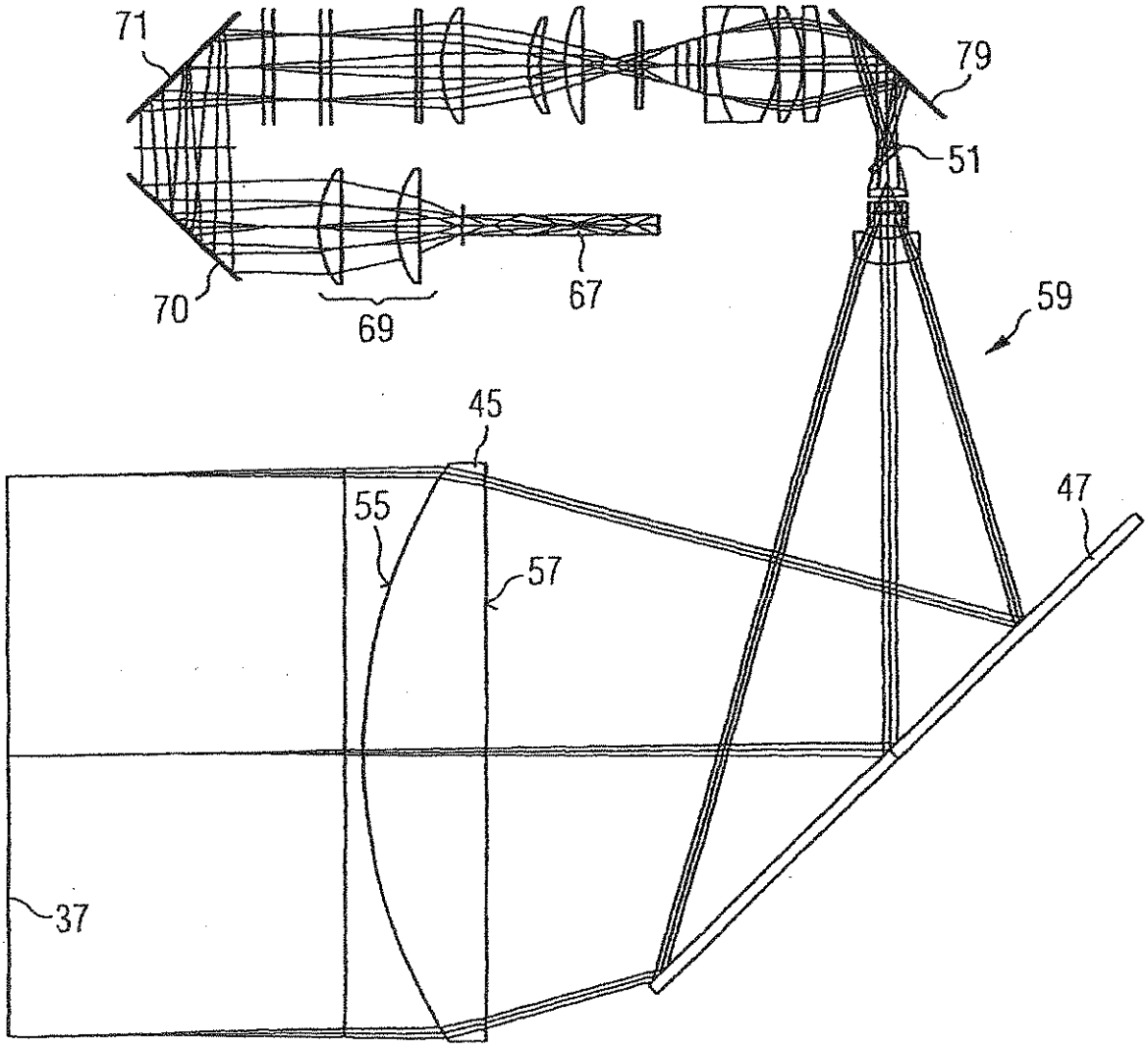


Fig. 3

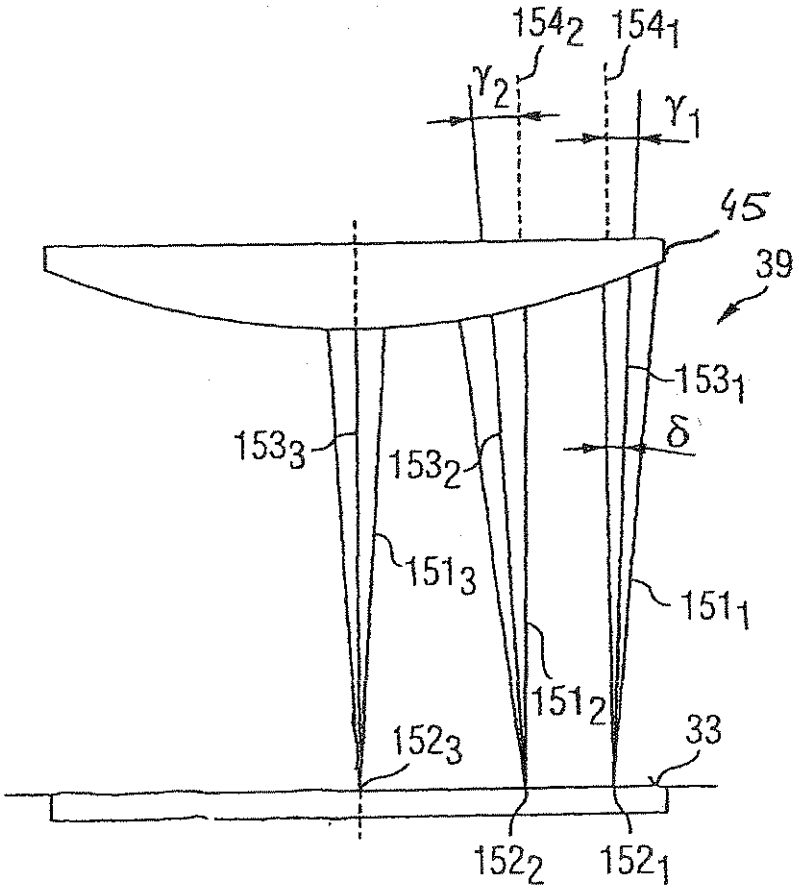

154_2
154_1
γ_2
γ_1
45
39
153_1
153_3
153_2
δ
151_3
151_1
151_2
152_3
33
152_2
152_1

Fig. 4

Fig. 5

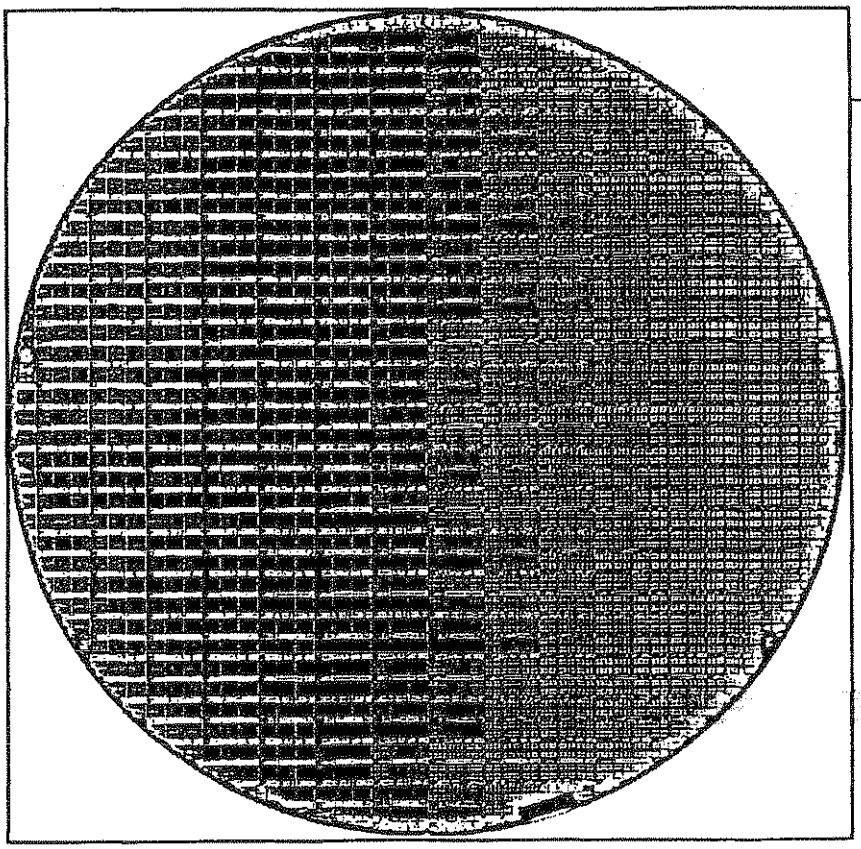


Fig. 6

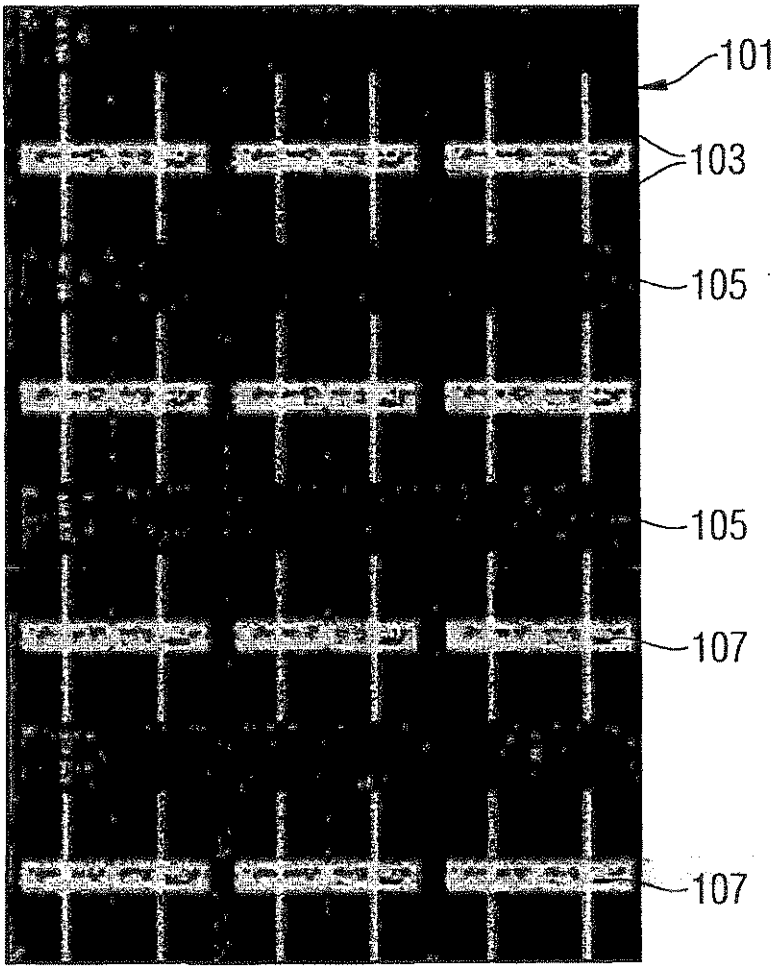


Fig. 7

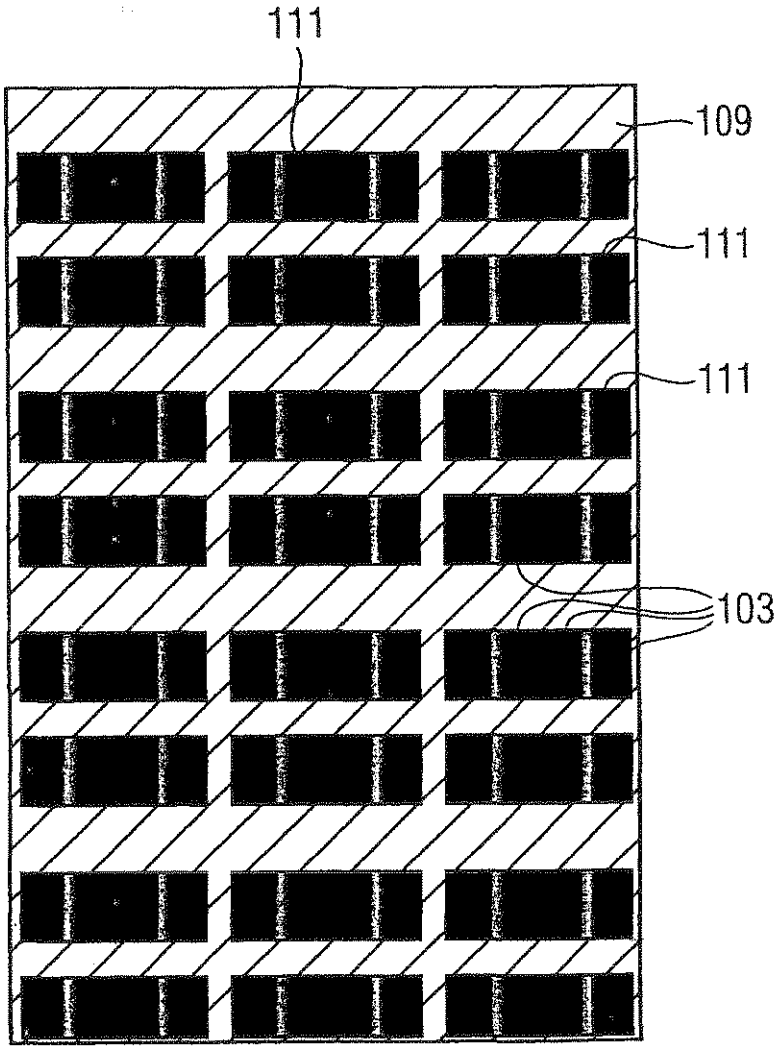
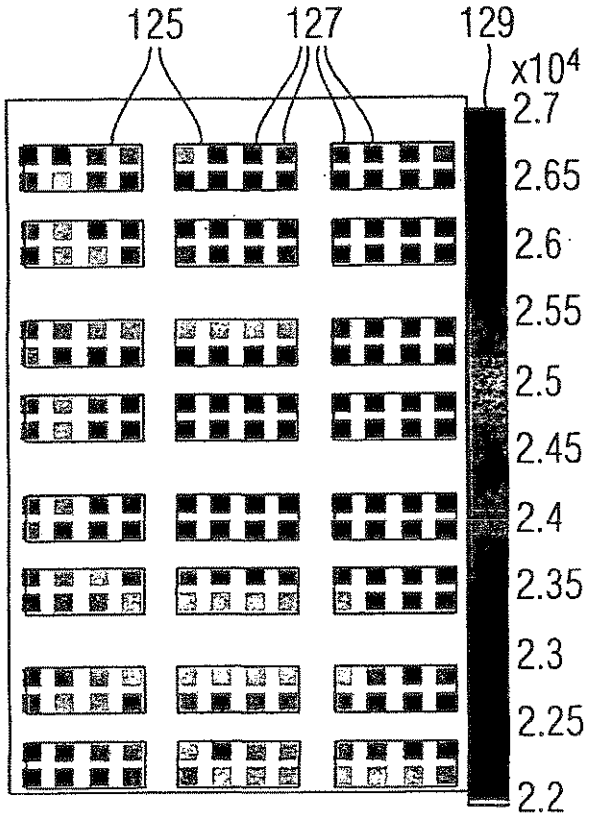


Fig. 8



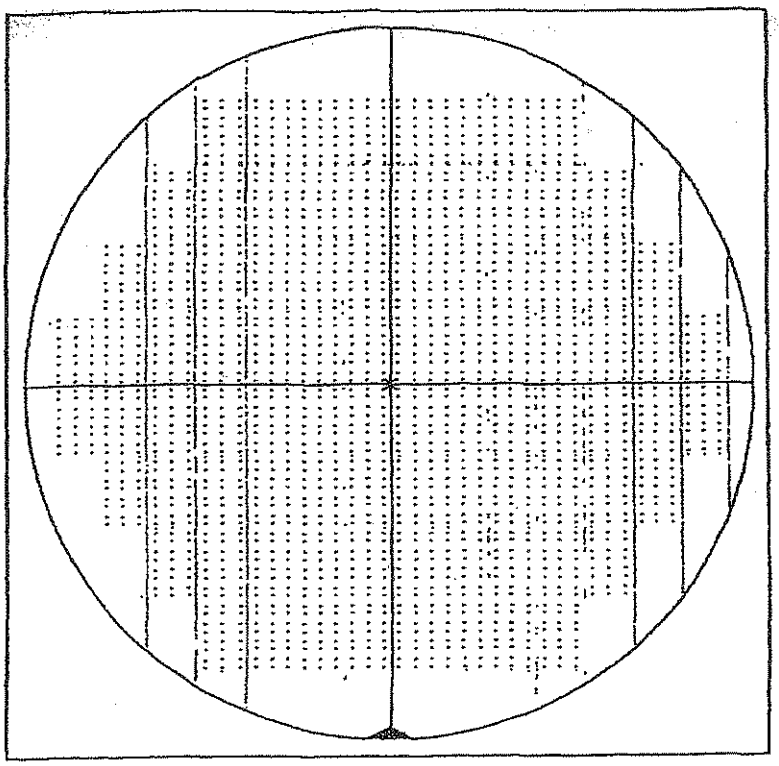


Fig. 9

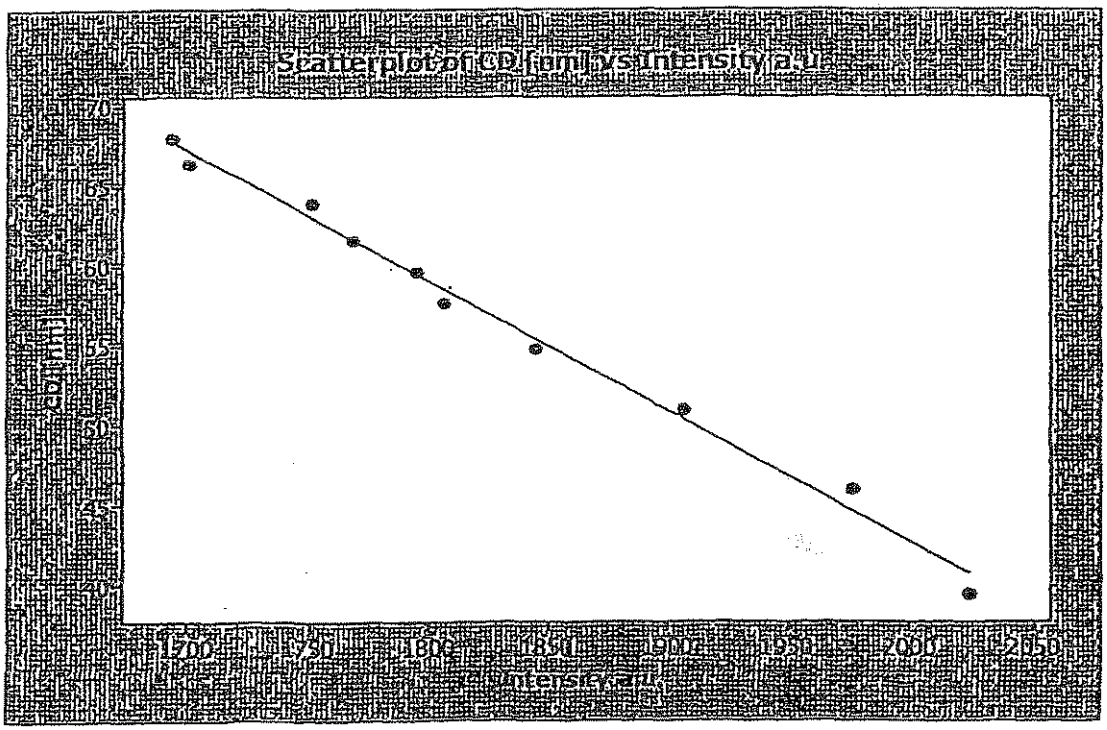

Scatterplot of CD [nm] vs Intensity [a.u.]
70
65
60
55
50
45
40
CD [nm]
1700
1750
1800
1850
1900
1950
2000
2050
Intensity [a.u.]

Fig. 10

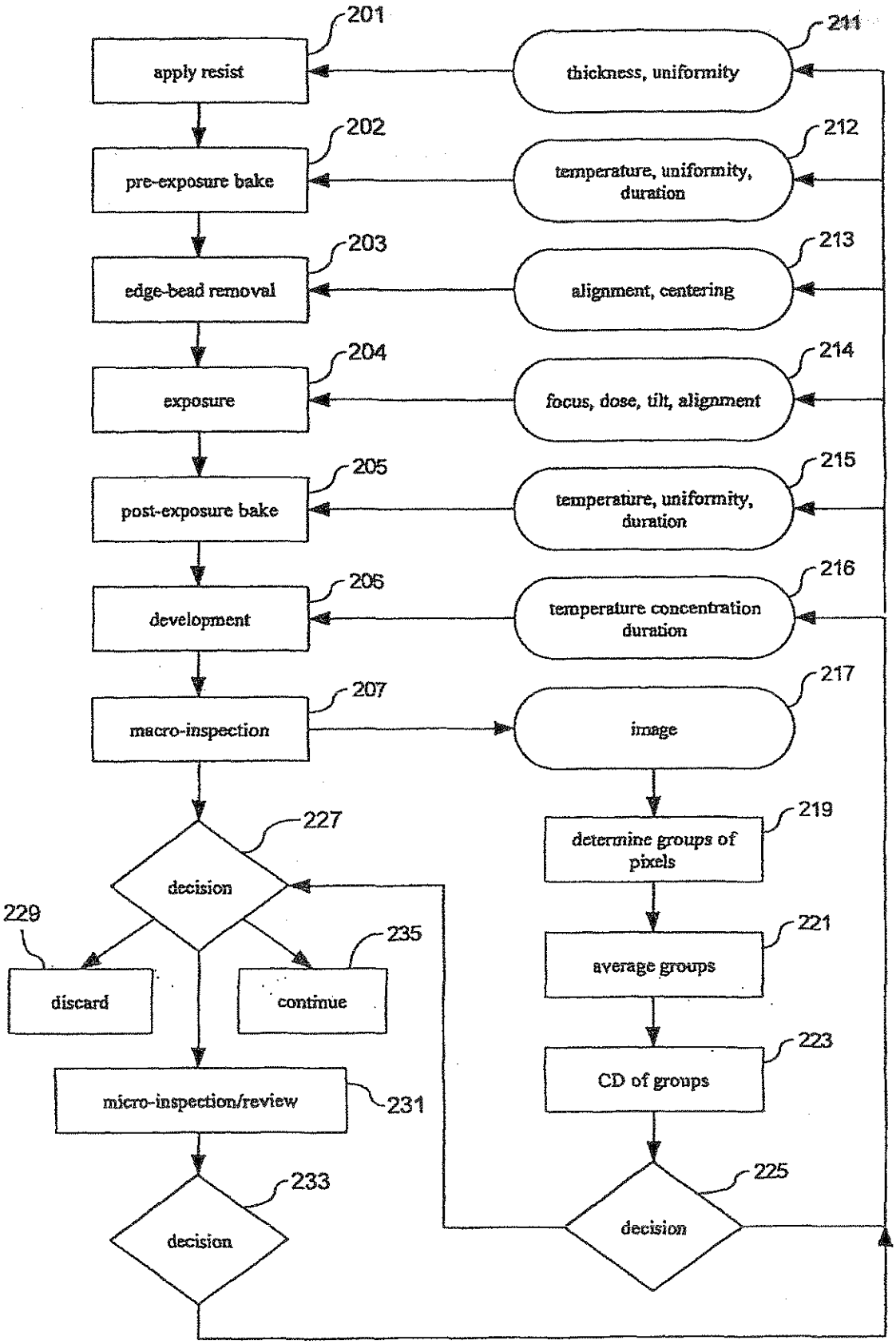

apply resist
201
thickness, uniformity
211
pre-exposure bake
202
temperature, uniformity, duration
212
edge-bead removal
203
alignment, centering
213
exposure
204
focus, dose, tilt, alignment
214
post-exposure bake
205
temperature, uniformity, duration
215
development
206
temperature concentration duration
216
macro-inspection
207
image
217
decision
227
determine groups of pixels
219
229
discard
continue
235
average groups
221
micro-inspection/review
231
CD of groups
223
decision
233
decision
225

Fig 11

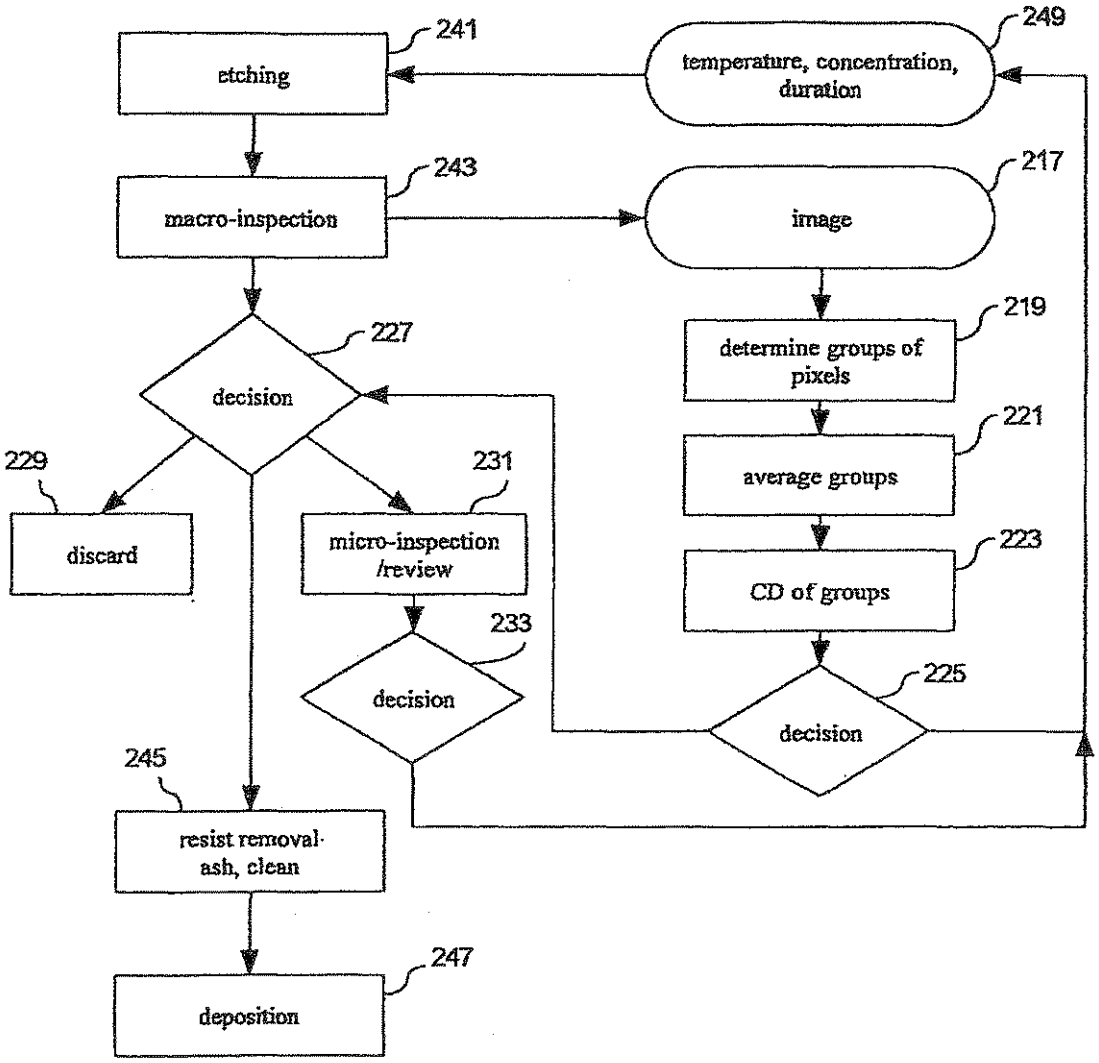

etching
241
temperature, concentration, duration
249
macro-inspection
243
image
217
decision
227
determine groups of pixels
219
average groups
221
CD of groups
223
discard
229
micro-inspection /review
231
decision
233
decision
225
resist removal· ash, clean
245
deposition
247

Fig 12

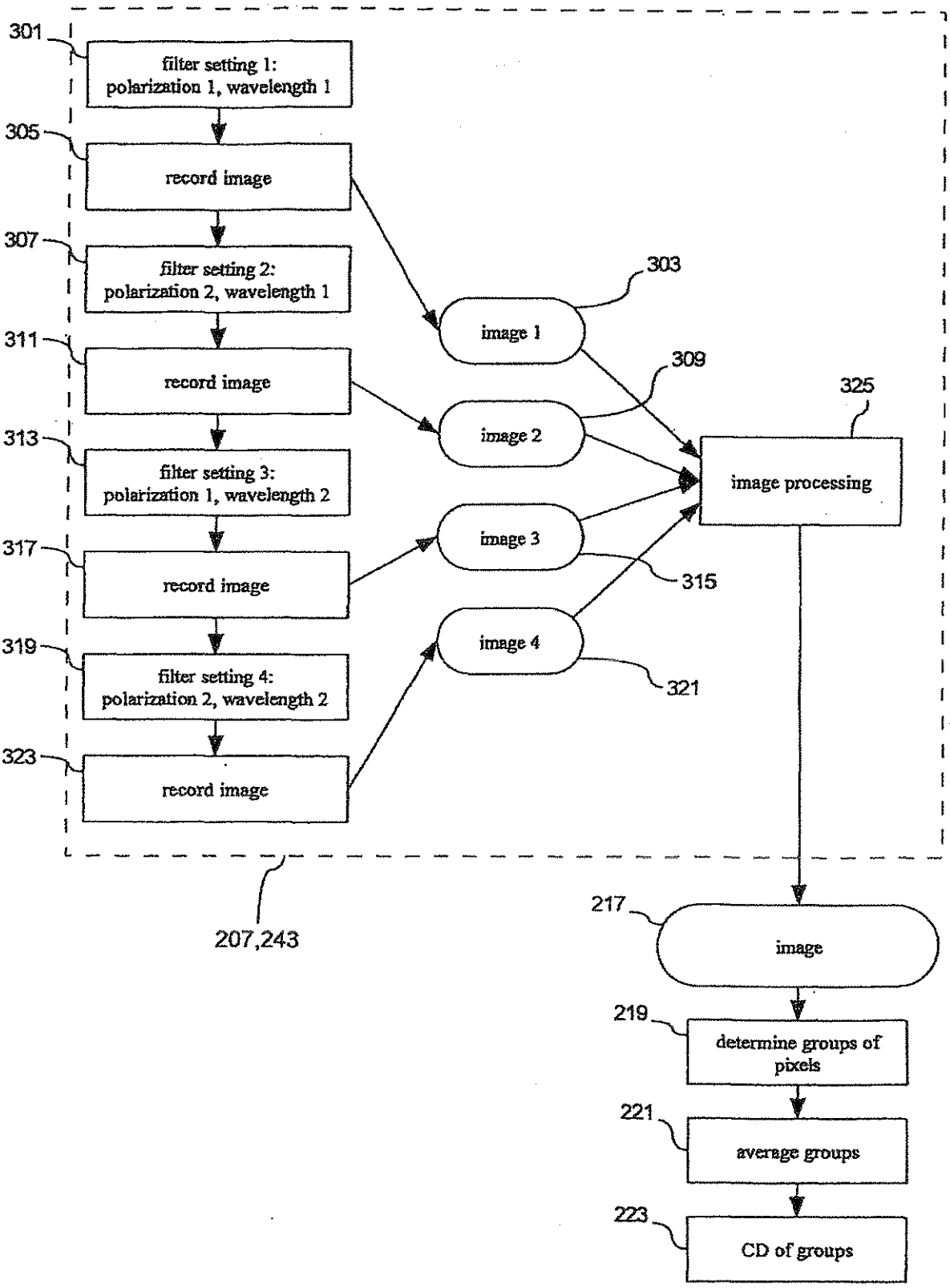

301
filter setting 1: polarization 1, wavelength 1
305
record image
307
filter setting 2: polarization 2, wavelength 1
311
record image
313
filter setting 3: polarization 1, wavelength 2
317
record image
319
filter setting 4: polarization 2, wavelength 2
323
record image
207,243
303
image 1
309
image 2
315
image 3
321
image 4
325
image processing
217
image
219
determine groups of pixels
221
average groups
223
CD of groups

Fig 13